

Darrel R. Tenney from NASA to Deliver Plenary Talk at the 1996 MRS Spring Meeting

Darrel R. Tenney, Chief of the Materials Division at the NASA Langley Research Center, will give his plenary presentation, "Materials Research: Changing Times, Trends, and Opportunities," at the 1996 MRS Spring Meeting in San Francisco. The plenary session is scheduled for April 8 at 6:00 p.m. in the Presidio Room, San Francisco Marriott.

As Chief of the Materials Division since August 1987, Tenney manages the overall operations of the division which is responsible for development of advanced materials for aircraft and spacecraft applications. The division is organized into five branches, conducting research in advanced composite materials, high performance polymers, adhesives, advanced aluminum alloys, metal-matrix composites, mechanics of materials, nondestructive

evaluation, and environmental effects on spacecraft and aircraft materials.

Tenney previously served as Assistant Chief of the Materials Division (1984-1987), and served as Head of the Applied Materials Branch within the division for three years. His previous assignments also included group leader and senior researcher.

Prior to joining NASA in 1974, Tenney was assistant professor of materials engineering at Virginia Tech where he received a PhD degree in materials engineering. He has been active in national technical societies including the Society for the Advancement of Material and Process Engineering, ASM International, and the American Society for Testing Materials, and serves on a number of advisory committees. He has been active

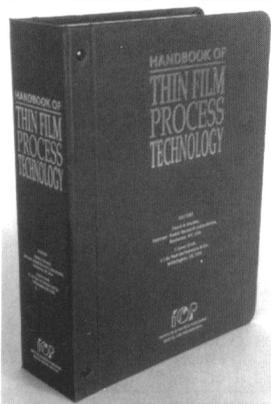


Darrel R. Tenney

in fostering international cooperation in space materials research. Tenney has coauthored more than 60 technical papers on materials. 

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